



JP11268438A2: IMAGE FORMING MATERIAL

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Application Number: JP1998000074630

IPC Class: B41N 1//14; G03F 7//004; G03F 7//032;

Abstract:

Problem to be solved: To provide an image forming material being suitable for a lithographic printing plate, which is excellent in image forming properties (a sensitivity, a development latitude).

Solution: This image forming material contains a polymer binder which is water-insoluble and soluble with an alkali aqueous solution, and an infrared ray absorber having a thermally decomposable sulfonate group. At unexposed parts, the infrared absorber having the thermally decomposable sulfonate group reduces the melting speed of an alkali-soluble polymer binder, and at exposed parts, a sulfonic acid of a coloring matter which is generated by a decomposition of the infrared ray absorber, increases the melting speed of the alkali-soluble polymer binder. By this method, a difference between both parts becomes larger, and a favorable image formation becomes possible.

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Family:



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Other Abstract Info: CHEMABS 131(15)206999Q DERABS C1999-470981

Foreign References: (No patents reference this one)



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What is claimed is:

1. A photosensitive negative image recording material for a planographic printing plate having an image recording layer containing the following components on a support:

- a compound (A) which is degraded by the action of light or heat to generate an acid,
- a cross-linking agent (B) which cross-links in the presence of an acid,
- at least one alkali-soluble resin (C),
- an infrared absorbing agent (D), and
- at least one amino acid or derivative thereof wherein the amino acid is selected from the group consisting of glycine, β -alanine, valine, norvaline, leucine, norleucine, phenylalanine, tyrosine, diiodotyrosine, surinamine, serine, proline, hydroxyproline, tryptophan, thyroxine, cystine, cysteine, γ -aminobutyric acid, glutamine, lysine, hydroxylysine, arginine and histidine.

Background/Summary: [Show background/summary](#)

Drawing Descriptions: [Show drawing descriptions](#)

Description of Preferred Embodiments: [Show description of preferred embodiments](#)

Foreign References:

Publication	Country	Date	IPC Class
EP1997000784233	European Patent Office (EPO)	7 /1997	

Other Abstract Info: CHEMABS 129(01)010678Y CHEMABS 129(01)010679Z DERABS C1998-337596 DERABS C1998-337597

Other References:

- A. Lamola. et al, Chemically Amplified Resists in Solid State Technology, Aug. 1991, pp. 53-60. (8 pages) [20 patents reference this \[Article info\]](#)

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